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Rapid oxidation of CVD-grown graphene using mild atmospheric pressure O2 plasma jet

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Abbreviations: MAPPJ, mild low damage atmospheric pressure plasma jet; GO, graphene oxide; UV, ultraviolet; MWCNTs, multi-walled carbon nanotubes, SLG, single layer graphene; Cu, copper; CVD, chemical vapor deposition; PMMA, poly(methyl methacrylate); XPS, X-ray photoelectron spectroscopy; CA, contact angle.

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